

ABSTRACT OF THE DISCLOSURE

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46 — A method of determining defect detection sensitivity data, comprises: taking image data from the  
5 desired surface areas of each of semiconductor devices,  
processing at least two of the image data through  
arithmetic operations and comparing the processed image  
data with a parameter of defect detection sensitivity  
substituted by predetermined threshold data to obtain  
10 information on defects in the desired areas at least in  
one-to-one correspondence with any of the image data  
arithmetically processed, repeating more than once the  
step of varying the parameter of the defect detection  
sensitivity to obtain the defect information, so as to  
52 — 15 obtain more than one sets of combination data on a value  
of the parameter of the defect detection sensitivity  
correlated with the defect information, processing more  
than one sets of the combination data to produce a  
mathematical function expressing a relation of the  
20 desired statistical data with the parameter of the  
defect detection sensitivity, the mathematical function  
being used to determine defect detection sensitivity  
data, the defect detection sensitivity data being used  
in obtaining the information on the defects in the  
25 desired surface areas of the semiconductor devices under  
defect inspection, and the defect detection sensitivity  
data defining an existence range of the defect  
information in the image data which are taken from the  
desired surface areas of each semiconductor device and  
30 which are arithmetically processed in the previous step.

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228 words